

Chemical Structure*) $ZRf_2Rf_6N(CF_2)_n Rf_8$ is $-CF_3$, $-CmF_{2m+1}$, or $-(CF_2)_q-SO_2-X-M^+$; Rf_6 and Rf_7 , independently, are perfluoroalkylene moieties having the formula $-CrF_{2r}$; n is 1-4; r is 1-4; m is 1-12; q is 1-4; and M^+ is a counterion.

5514518

**METHOD OF IMPROVING
DELAMINATION IN AN IMAGE
FORMING MATERIAL UTILIZING
2-DIAZO-1,2-QUINONE COMPOUNDS
HAVING FLUORINE CONTAINING
SUBSTITUENT GROUPS**

Wakamatsu Kan; Wakata Yuichi; Satomura Masato; Namiki Tomizo Shizuoka, JAPAN assigned to Fuji Photo Film Co Ltd

A 2-diazo-1,2-quinone compound having a substituent group containing an alkyl group which is substituted by at least one fluorine atom is described. This compound has a capacity to change its polarity when exposed to light. The invention also provides an image forming material in which the invention compound is added to at least one of laminated layers. When these laminated layers are exposed to light, the adhesiveness of the compound-containing layer to its adjoining layer is reduced effectively due to the polarity-changing ability of the compound, thus making the easy delamination of the layers possible. This compound is applicable to many instances in which image receiving sheets are used, such as the formation of a multi-color image by a transfer method (a color proof, for example) and the preparation of a printing plate of the delamination development type.

5514526

**FLUORINE-CONTAINING COMPOSITION
FOR FORMING ANTI-REFLECTION
FILM ON RESIST SURFACE AND
PATTERN FORMATION METHOD**

Nishi Mineo; Makishima Hideo Kitakyushu, JAPAN assigned to Mitsubishi Chemical Corporation

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Sec. 102(e) Date Feb. 2, 1994 PCT Filed May 27, 1993 PCT Pub. No. WO93/24860 PCT Pub. Date Dec. 9, 1993. A composition for forming anti-reflection film on resist surface which comprises an aqueous solution of a water soluble fluorine compound, and a pattern formation method which comprises the steps of coating a photoresist composition on a substrate; coating the above-mentioned composition for forming anti-reflection film; exposing the coated film to form a specific pattern; and developing the photoresist, are provided. Since the composition for forming anti-reflection film can be coated on the photoresist in the form of an aqueous solution, not only the anti-reflection film can be formed easily, but also, the film can be removed easily by rinsing with water or alkali development. Therefore, by the pattern formation method according to the present invention, it is possible to form a pattern easily with a high dimensional accuracy.

5514720

**STABLE EMULSIONS OF HIGHLY
FLUORINATED ORGANIC COMPOUNDS**

Clark Leland C; Shaw Robert Cincinnati, OH, UNITED STATES assigned to HemaGen/PFC

Stable emulsions of highly fluorinated organic compounds for use as oxygen transport agents, artificial bloods or red blood cell substitutes and as contrast agents for biological imaging. The emulsions comprise a highly fluorinated organic compound, an oil that is not substantially surface active and not significantly soluble in water, a surfactant and water.

5514724

**DIMENSIONALLY STABLE CLOSED
CELL RIGID POLYISOCYANATE BASED
FOAM PREPARED FROM A FROTH
FOAMING MIXTURE**

Green Todd J; Tucker John R Canton, MI, UNITED STATES assigned to BASF Corporation